

Resource Summary Report

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Texas State University Rapid Thermal Annealer

RRID:SCR_028204

Type: Tool

Proper Citation

Texas State University Rapid Thermal Annealer (RRID:SCR_028204)

Resource Information

URL: <https://sro.txst.edu/sro-facilities/sro-nrsc/sro-nrsc-rtp.html>

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Description: Facility AGA Heatpulse 610 is a benchtop rapid thermal annealer (RTA/RTP) that utilizes high power lamps to heat treat thin films and substrates for processes such as contact formation, silicide formation, and dopant diffusion/activation. Temperature control via PID loop has a maximum heating rate of ~50 C/s and maximum temperature of 1000 C. The chamber can also be atmospheric purged with N₂, Ar, 4% H₂ in Ar, or O₂. A rapid thermal processing system that enables fast heating and cooling cycles for semiconductor wafers, used for dopant activation, oxidation, and material modification.

Synonyms: Rapid Thermal Annealer (AS-One 150)

Resource Type: instrument resource

Keywords: rapid thermal annealing, RTA, semiconductor processing, thermal treatment, dopant activation

Availability: Restricted

Resource Name: Texas State University Rapid Thermal Annealer

Resource ID: SCR_028204

Alternate URLs: <https://sro.txst.edu/sro-facilities/sro-nrsc.html>

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Ratings and Alerts

No rating or validation information has been found for Texas State University Rapid Thermal Annealer.

No alerts have been found for Texas State University Rapid Thermal Annealer.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.